EXPOSURE REQUEST FORM

Please forward one week before exposure request, to Craig Stevens (Tel. 225-578-4603), located at CAMD/LSU, 6980 Jefferson Highway, 70806, Room 106. The samples should accompany the routing sheet or be deposited at the facility, in the "User Box".

Project Reference Number (PRN):				
Contact Person: Pho		e:	E-mail:	
SAMPLE DESCRIPTION AND F	EXPOSURE PA	RAMETER	<u>s</u>	
Sample Name:				
Resist Type:		Resist Thio	ckness:	(µm)
Substrate Material:		Size:		(cm)
Mask Name:		Mask Form	nat:	
Mask Membrane Material and Thi	ickness:			(µm)
Thickness of SU-8 Layer remainir	ng on the mask: _			(µm)
Ring Energy:	(Gev)	Beamline:		
Filter Material and Thickness:		(µm)	He Pressure:	(torr)
Proximity Gap: (µm)	1			
Min. Bottom Dose:	(J/cm3)	Max. Ratio	of Top to Bottom Dose: _	
Scan Length: (c	m or inch)	Aperture re	equired:	(cm)
Dose per cm: (n	nA.min/cm)	Total Dose	2:	_(mA.min)
Cooling required: □ mask & subs	trate □ mask on	ly □ no cool	ling	
Exposure will be performed by us	er □ Yes □ No			
CAMD OFFICE USE ONLY				
Date received at CAMD:		Approved	by:	
Anticipated exposure date at CAME	D:			
Exposure performed at CAMD by:		at	Beamline on Date:	
Date notified to pick up:	Date pick	ed up:	by:	

Form Revised: <u>01/2009</u>